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Abstract of the Disclosure

An arc chamber filament for an ion implanter used to implant ions in a semiconductor wafer substrate during the fabrication of integrated circuits on the substrate. The filament includes a pair of parallel filament segments each of which is connected to a voltage source at one end. The parallel filament segments are connected to each other through a bidirectional winding configuration which defines at least one generally U-shaped winding unit on each side of a plane of symmetry bisecting the filament.